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I WER DI	AL	Shudi NAKAMURA	. "Curren	t Status	and Future	Prospe	ects of .	LnGan-	
R		Based Laser Di	odes," JS	AP Inter	national, J	an. 200	00, Tokus	shima,	
	AM	Japan, pp. 5-1 Masaru KURAMOT	n et al.	"Toward:	a Durable	InGaN	MQW LD-	Room	
(AVI	Temperature CW Develop., V. 4	<i> Operation</i>	on of InGa	an MQW Lase	r," NE	C Res. &		
) -	AN	Shudi NAKAMIRA	et al.	"InGaN/G	aN/AlGaN-Ba	sed La	ser Diod	es with	
(AIN	Modulation-Dor	ed Strair	red-Layer	Superlatti	ces,"	Jpn. J. Z	Appl.	
\rightarrow	1	Phys., V. 36,	al. "Thi	ck GaN E	oitaxial Gr	owth w	ith Low		
	AO	Akira USUI et al., "Thick GaN Epitaxial Growth with Low Dislocation Density by Hydride Vapor Phase Epitaxy," Jpn. J. Appl. Phys., V. 36, 1997, pp. L899-L902.							
	1	Appl. Phys., \ Shigefusa CHIO	7. 36, 199	patially	Resolved Ca	thodol	uminesce	nce	
	AP	Spectra of Inc	SaN Quantı	ım Wells,	" Appl. Phy	s. Let	t. /1, 1	997, pp.	
AQ W. W. CHOW et al., "Microscopic Theory of Ga Quantum Well Laser," Appl. Phys. Lett. 71, 1 AR A. Atsushi YAMAGUCHI et al., "Optical Recomb							[997, pp. 2608-2610.		
	AR	High-Quality (Initiated Epit Apppl. Phys	GaN Films taxial La V. 39, 2	and InGa teral Ove 000, pp.	N Quantum W rgrown GaN 2402-2406.	Substr	rown on ates," J	pn. J.	
	1.0	G. Martin et	al., "Val	ence-Band	Discontinu	ities	of Wurtz	ite GaN,	
V	AS	AlN, and InN Spectroscopy,	Heterojun " Appl. P	ctions Me hys. Lett	asured by X	с-кау Р . pp. 2	541-2543		
V	AS	AlN, and InN Spectroscopy,	Heterojun " Appl. P	ctions Me hys. Lett	asured by X	рр. 2	541-2543		

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